# CITY OF ELKHART, INDIANA INDUSTRIAL WASTE QUESTIONNAIRE

SEC	TION A. GENERAL INFORMATION (Type or Print, Please)
1.	Company NameIdeal Plating Corporation
2.	Mailing Address P.O Box # 74
3.	Address of Premises 1913 South 14th Street
4.	Name and Title of Signing Official Peggy Cipollo, President
5.	Wastewater discharges to:
	City sewer system Yes
	Private septic system <u>No</u>
6.	If your facility discharges to the City sewer system, check the types of discharges:
	X Sanitary Wash water X Rinse water
-	X Cooling water X Process water Scrubber water
	Other None
	Note: If your facility discharges only to a private septic system and not to the City sewer system, or if only sanitary sewage is discharged to the City sewer system, it is only necessary to fill out Section A of this questionnaire. Otherwise, complete entire questionnaire.
7.	Contact Official
	Name Nick Cipollo
	Title Vice President, Oporations
	Address 1913. South 14th Street
	Phone Number <u>293-5668</u>
	The information contained in this questionnaire is familiar to me and to the best of my knowledge and belief, such information is true, complete, and accurate.
	12-19-83 Juan Cipilly
	Date Signature of Official

## SECTION B. PRODUCT OR SERVICE INFORMATION

	Brief description of manufacturing or service activity on premises:
	Ideal Plating Corporation, is a Small Job Shop Oporation
-	Providing Plating Services For Customers in Northern
	Indiana And Southern Michigan, Specalizing in Zinc Pla
]	Principal Raw Materials Used:
	Steel Stampings.Together with some Brass.
	Catalysts, Intermediates:
	None
	Principal Product or Service (use Standard Industrial Classification
	Manual if appropriate): 3471
	Appended to this questionnaire is a list of Standard Industrial Classification (SIC) codes for industries currently or potentially subject to USEPA preteatment regulations. List SIC codes for
	each of your processes that are subject to USEPA pretreatment regulations.

SEC	CTION C. PLANT OPERATIONAL CHARACTERISTICS	
1.	Type of Discharge: X Batch X Continuous X Both	
	For batch discharges, list types, average number of batches/24 hrs.	
	and volume (gallons) per batch. spent,acid/alkaline 2 batches./80	
	Production Hrs/ 600-gol.	
2.	Is there a scheduled shutdown? Yes	
	When? Week-Ends And Holidays	
3.	Is production seasonal? No	
	If yes, explain indicating months(s) of peak production.	
		•
	N/a	
4.	Average number of employees per shift: 15 lst; 5 2nd; (5 3rd Part Tim	е
5.	Shift start times: 6.60 1st; 2.30 Pm 2nd; 10.30 3rd Part tim	9
6.	Shifts normally worked each day of the week:	
	Sun Mon Tue Wed Thu Fri Sat	
	lst <u>x x x x x</u>	
	2nd <u>X X X X X</u>	
	3rd X X X X (As Required)	
7.	Describe any wastewater treatment equipment or processes in use:	
	Acid/Alkaline, neutralization, collection and Desposal	
	of hazardous/toxic Plating Waste, per Attached Continge-	
	ncy Plan, 40CFR Part 265.50 265.56	
	Note' above#7. applys to in house processes and simple	
	pollution control practices	

## SECTION D. WATER CONSUMPTION AND LOSS

THE THE PARTY OF T	1000		
Raw Water Sources:			
Source	Quant	ity	
Elkhart City Water		000 gallons	per day
None		gallons	per day
None		gallons	per day
None		gallons	per day
Nater treatment processes in	use:		
none Chemical coagulation, polymers, etc.	including use o	f alum, ferric	chloride
none Lime softening		·	
none Resin (ion exchange)	water softening		
none Filtration			
none Chemical (chlorine or	ozone) disinfec	tion	
Others See # 7 or	n page #3		
****			
List Water Consumption in Plan	nt:	•	·
List Water Consumption in Plan		gallons per	day
	10.000	gallons per gallons per	•
Cooling Water	10.000	- · · · · · -	day
Cooling Water Boiler Feed	10.000 none	gallons per	day
Cooling Water Boiler Feed Process Water	10.000 none 24.700	gallons per	day day day

\*Sanitary flow can be estimated at 10 gpd per employee.

4.	List average	volume of discharg	e or water loss	to:	
	City Wast	ewater Sewer	34.850	gallons	per day
	Septic Ta	nk Discharge	none	gallons	per day
	Surface D	ischarge	_186	gallons	perday
	Waste Hau	ler	10	gallons	per day
	Evaporati	on	100	gallons	per day
	Contained	in Product	none	gallons	per day
5.	Is Discharge	to Sewer:	Intermittent	X	Steady
6.	List averag B-5 above:	e water usage for	SIC Processes	itemize	d in Section
	Regulated SIC No.	Brief Process D	escription		age Water mption(GPD)
	3471	Electroplati	ng	34.	000
		****			
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#### SECTION E. SEWER CONNECTION AND DISCHARGE INFORMATION

1.	List plant sewer	outlets and	flow: (assign	sequential reference
	number to each sew	er starting wi	th No. 1).	

Reference No.	Descriptive Location of Sewer Connection or Discharge Point	Avg. Flow (gpd)
# 1	(Manhole) Plating Dept. See Sketch	34.850
# 2	Front of Blds, SO 14th Street	34.850

- 2. Attach a scaled drawing or dimensioned sketch of the industrial complex showing location of sewer referenced in E-1 above and location of the SIC process described in Section D-5. Show location of monitoring manhole, if any, and other possible sampling points for sewers and SIC process effluents. Indicate how City industrial monitoring staff can gain access to the sampling points. For reference and field orientation buildings, streets, alleys, and other pertinent physical structures should be included.
- 3. Is plant required to prepare a Spill Prevention Control and Countermeasure (SPCC) Plan per 40 CFR 112 or a RCRA Contingency Plan?

  Yes If report has been prepared, attach copy. Copy attached.

  If report is required, but has not yet been prepared; indicate date when it will be submitted.

#### SECTION F. PRIORITY POLLUTANT INFORMATION

1. Please indicate by placing an "X" in the appropriate box by each listed chemical whether it is Suspected to be Absent, Known to be Absent, Suspected to be Present, or Known to be Present in your manufacturing or service activity or generated as a byproduct. Some compounds are known by other names. Please refer to Appendix A for those compounds which have an asterisk(\*).

ITEM NO.	CHEMICAL COMPOUND	SUSPECTED	KNOWN	SUSPECTED	KNOWN	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED	KNOWN	SUSPECTED	KNOWN
1.	ammonia			х		47.	chlorobenzene	x		ļ	
2.	asbestos (fibrous)	х			~~	48.	chloroethane*	X			
5.	cyanide (total)				Х	49.	2-chloroethylvinyl ether	Х			
						50.	chloroform*	Х		1	
4.	antimony (total)	х				51.	chloromethane*	X	i		T
3.	arsenic (total)		X			52.	2-chloronaphthalene	Х			
5.	beryllium (total)	x				53.	2-chlorophenol*	x	Ī		1
<del></del>	cadmium (total)			х		54.	4-chlorophenylphenyl ether	X		i	
3.	chromium (total)				X	55.	chrysene*	X			1
9.	copper (total)			X		56.	4,4'-000*	Х	ì	į .	
10.	lead (total)		Х			57.	4,4'-DDE*	x	İ		
11.	mercury (total)		X			58.	4,4'-DOT*	lх	i		
12.	nickel (total)		1	X		59.	dibenzo(a,h)anthracene*	X	i		
13.	selenium (total)		X			60.	dibromochloromethane*	X	i	i	
14.	silver (total)	X	1.55	i	1	61.	1,2-dichlorobentene*	X	<u> </u>	Í	1
15.	thallium (total)	X	i	İ	1	62.	1,3-dichlorobenzene*	X	!	!	
16.	linc (total)				X	63.	1,4-dichlorobenzene*	x	1	ł	
					1	64.	3,3'-dichloropenzidine	X		1	
l	acenapiithene	X				65.	dichlorodifluoromethane*				
13.	acenaphthylene	Х				66.	l,l-dichloroethane*	X			<u> </u>
19.	lacrolein	X				67.	1,2-dichloroethane*		Х	i	1
20.	acrylonitrile	X		Ĭ		68.		X		!	1
21.	aldrin	Х			<u> </u>	69.	trans-1,2-dichloroethene	X	1	1	<u> </u>
22.	anthracene	X				70.	2,4-dichlorophenol	X	<u>i</u>	1	<u> </u>
23.	beniene	Х	1	<u> </u>	<u> </u>	71.	1,2-dichloropropane*	X	!		<del>-</del>
24.	benzidine	Х		↓		72.	(cis & trans)1,3-dichlo-	·	1	1	
25.	benzo(a)anthracene*	X	<u> </u>	<u> </u>	1	<u> </u>	ropropene	<u> </u>	!	ᆚ	<del> </del>
26.	benio(a)pyrene*	X	<del> </del>		<del> </del>	75.	dieldrin	<u> </u>	-	1	!
127.	benzo(b)fluoranthene	X	<u> </u>	ļ	<u>.</u>	74.	diethyl phthalate*	+x	. i	,	<del>-</del>
28.	penzo(g,h,i)perylene*	Х	<u> </u>	<u> </u>	-	-5.	2,4-dimethylphenol*	<u> X</u>	<u>;</u>	<u> </u>	<del></del>
29.	benzo(k)fluoranthene*	X	<del></del>	<del> </del>	<u> </u>	76.	dimethyl onthalate	<u> </u>			<del>-</del>
30.	a-BHC (alpha)	Х	<del> </del>	i		77.	di-n-butyl phthalate	12	!		<del></del>
31.	15-BHC (beta)	Х	1	<del> </del>	<del></del>	78.	di-n-octyl phthalate*	<u> </u>	واحتاناه التعليات	i	-
32.	d-BHC (delta)	Х	+	<del>                                     </del>	+	79.	4,6dinitro2-methylphenol		<del></del>	1	<u> </u>
33.	g-BHC*(gamma)	X	<del> </del>	+	+	80.	2,4-dinitrophenol	1X		<del>-</del>	
34.	bis(2-chloroethyDether		-	-	_	81.	2,4-dinitrotoluene	1 2	<u> </u>	<u> </u>	
35.	bis2-chloroethoxymethare		1	+	+	i 82. i 83.	2,6-dinitrotoluene	<del>'</del> x	<del></del>	( ************************************	-
	bis2-chloroisopropyletne		+	<del></del>	+	33.	1,2-diphenylhydrazine*	ŤX.	<del></del>	-	+-
37.	bis(chloromethyliether*		+	+	+	1 85.	endosulfan II*	X		+	<del>-</del>
-	bis2-ethylhexyllonthalate		<del></del>	<del>_</del>	+	36.	endosulfan sulfate		<u> </u>		+
39.	bromodichloromethane*	X.	+	-		1 87.	lendrin	X		-	<del></del>
10.	والمرافع المرافع والمرافع	X	+	+	+	88.	jendrin aldehyde	<u></u>	_	+	<del></del>
11.	4-promomethane	X.	<del></del>	+-		1 89.	ethylbeniene	X_			<del></del>
12.		X	+	+	+	90.	fluoranthene	*		<del></del>	
43.	butylbenzyl phthalate carbon tetrachloride*	-	+	+-	<del>+</del> -	91.	fluorene*	<u></u>	_	<del></del>	
15.	chlordane	X	+-	+	<del></del>	92.	heptachlor	X		+	
	4-chloro-3-methylphenol	X	+-	<del></del>	+	1 93.	heptachlor epoxide	X	1	1	
+0.	M-cutoro-a-merny thushot.	$\mathbf{x}$	1		1	1 33.	meptachiot epoxide	_X	<u> </u>	1	

SECTION F. PRIORITY POLLUTANT INFORMATION (CON'T)

ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN	SUSPECTED PRESENT	KNOWN	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED	KNOWN ABSENT	SUSPECTED PRESENT	KNOWN
94.	hexachlorobenzene*		X		1	112.	PCB-1248*	LX			
95.	hexachlorobutadiene		X		1	113.	PCB-1254*	l y			
96.	hexachlorocyclopenta-		X		14	114.	PCB-1260*	1 4			
	diene*		×			115.	pentachlorophenol	IV			
97.	hexachloroethane*		×			116.	phenanthrene	11			
98.	indeno(1,2,3-cd)pyrene*		×		100	117.	phenol	17			
99.	isophorone*		×			118.	pyrene	11/			
100.	methylene chloride*		×			119.	2,3,7,8-tetrachlorodi-	LX			
101.	naphthalene		X		Ī.,		benzo-p-dioxin*	X			
102.	nitrobenzene		X			120.	1,122-tetrachloroethane"	X			
103.	2-nitrophenol*		X			121.	tetrachioroethene*	l v			
104.	4-nitrophenol*		X			122.	toluene*	l v			
105.	n-nitrosodimethylamine*		Y			123.	toxaphene	ΙV			
106.	n-nitrosodipropylamine*		1×			124.	1,2,4-trichlorobenzene	1 X			
107.	n-nitrosodiphenylamine*		×			125.	l,l,Ltrichloroethane	V			
108.	PCB-1016*		14			126.	1,1,2-trichloroethane*	IX			
109.	PCB-1221*		V			127.	trichloroethene*	X			
110.	PC3-1252*		X		1	128.	trichlorofluoromethane	X			
, 111.	I PC3-1242*		Y	T		129.	2,4,6-trichlorophenol	īΧ			
	:		1 )			130.	vinyl chloride*	1 /		1	

2. For chemical compounds in F-2 above which are indicated to be "Known Present," please list and provide the following data for each: (attach additional sheets if needed).

		<del></del>	<del>,</del>	<del>,</del>	<u> </u>		<del>,</del>
ITEM NO.	CHEMICAL COMPOUND	ANNUAL USAGE(LBS)	ESTIMATED LOSS TO SEWER LBS./YR,	ITEM NO.	CHEMICAL COMPOUND	ANNIAL USAGE (LBS)	ESTINATED LOSS TO SEWER LBS./YR.
3	CYANIDE	4.800	300				
8	CHROMIUM	150	50				
16	ZINC	6.000	150				
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	None
4.	Describe, what if any, laboratory analyses have been conducted on process waste streams in the plant, including which streams were sampled, what parameters were measured, and frequency and type of samples. (The baseline report referred to in G2 below can be referenced in answering this question.)
	24/hr composite samples are taken on a quartly bases
	(all process streams) Laboratory analysis are ran for t
	Following CN/zn/bod/SS/PH,
SEC	TION G. PRETREATMENT
1.	Is this plant subject to an existing Pretreatment Standard?
	ves
2.	Is this plant required to submit a baseline report per 40 CFR 403.12? If a baseline report has been prepared, attach a copy to this questionnaire. Copy attached If a baseline report is required, but has not yet been prepared, indicate date that it will be submitted. 1984/18+/q+r
	If subject to Federal Pretreatment Standards, are the standards being met on a consistent basis? (The baseline report can be
3.	referred to in answering this question.)
3.	referred to in answering this question.)  This facality plans on compliance to part 413 of the

	P	re-Tre	atmen	t Equ	<u>lipmer</u>	nt is	requi	<u>red t</u>	o mee	<u>t</u>
	disc	harge	standa	ards	to a	POTW	(see	#3 s	e <b>cti</b> or	n c Pa
	<del>70°2°,,,,</del>	~ · · · · · · · · · · · · · · · · · · ·						<u></u>		
01	escribe result	at yo	ur fac	ility	and .	the me	thods	employ	ed to	dispos

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